 INFORMATION DISCLOSURE CITATION <small>(Use several sheets if necessary)</small>				ATTY DOCKET NO. 14002-7		SERIAL NO. TBD	
				Chou et al.			
				FILING November 12, 2003		GROUP TBD	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BT		4,592,081	05/27/1986	Eaton et al.			
		4,211,489	07/08/1980	Kleinknecht et al.			
		2,302,024	11/17/1942	Goss, Jr.			
		3,742,229	06/26/1973	Smith et al.			
		3,951,548	04/20/1976	Westell			
		4,037,325	07/26/1977	Weber et al.			
		4,200,395	04/29/1980	Smith et al.			
		4,475,223	10/02/1984	Taniguchi et al			
		4,588,468	05/13/1986	McGinty et al.			
↓		4,883,563	11/28/1989	Kotani et al.			
BT		6,056,526	05/02/00	Sato			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
BT		1196749	01/30/1988	Japan w/English Abstract			
↓		244884	03/28/1986	European			
↓		4255307	09/10/1992	Japan w/English Abstract			
BT		4332694	08/05/1991	Japan w/English Abstract			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
BT		Broers, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter</u> 33 (5), 1978 American Institute of Physics, 392-394, (September 1, 1978)					
BT		Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science</u> , Vol. 272, 85-87, (April 5, 1996)					
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INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> 3-16-04				ATTY DOCKET NO. 14002-15		SERIAL NO. TBD		
				Chou et al.				
				FILING November 12, 2003		GROUP TBD		
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
BT		5,352,394	10/04/1994	Fujita et al.				
		3,743,842	07/03/1973	Smith, H.I., et al.				
		4,310,743	01/12/1982	Seliger, R.L.				
		4,383,026	05/10/1983	Hall, T.M.				
		4,450,358	05/22/1984	Reynolds, G.O.				
		4,498,009	02/05/1985	Reynolds, G.O.				
		4,516,253	05/07/1985	Novak, W.T.				
		4,552,615	11/12/1985	Amendola, A., et al.				
		4,576,678	03/18/1986	Shibata, H.				
		4,606,788	08/19/1986	Moran, P.L.				
BT		4,731,155	03/15/1988	Napoli, L.S., et al.				
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
BT		9117565	11/14/1991	PCT				
BT		98/26913	06/25/1998	PCT				
BT		WO 93/21671	10/28/1993	PCT				
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
BT		Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering 11</u> , Elsevier Science Publishers B.V., 317-321, (1990)						
BT		Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter 62 (23)</u> , 1993 American Institute of Physics, 2989-2991 (June 7, 1993)						
EXAMINER Binh Tran				DATE CONSIDERED 3/3/06				
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INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> 3-16-04				ATTY DOCKET NO. 14002-15		SERIAL NO. TBD	
				Chou et al.			
				FILING December 10, 2003		GROUP TBD	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
B5		3,833,303	09/03/1974	Burns et al.			
		4,325,779	04/20/1982	Rossetti, J.J.			
		4,832,790	05/23/1989	Rossetti, J.J.			
		5,277,749	01/11/1994	Griffith, J.H., et al.			
		5,861,113	01/19/1999	Choquette, S.J., et al.			
		5,032,216	07/16/1991	Felten			
		5,152,861	10/06/1992	Hann			
		4,664,862	05/12/1987	Ghavamikia			
		5,253,409	10/19/1993	Bier et al.			
✓		5,234,571	08/10/1993	Noeker			
B5		4,738,010	04/19/1988	Ehrfeld et al.			
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
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B5		Hara, et al., "An Alignment Technique Using Diffracted Moire Signals", <u>J. Vac. Sci. Technol. B7 (6)</u> , 1989 American Vacuum Society, 1977-1979, (Nov./Dec. 1989)					
B5		Harmening, et al., "Molding of Threedimensional Microstructures by the Liga Process" <u>Proceedings IEEE: Micro Electro Mechanical Systems</u> , Travemunde, Germany, 202-207, (1992)					
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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary) 3-16-04	ATTY DOCKET NO. 14002-7	SERIAL NO. TBD
	Chou et al.	
	FILING November 12, 2003	GROUP TBD

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BT	5,119,151	06/02/1992	Onda			
	4,781,790	11/01/1988	Wu			
	4,788,015	11/29/1988	Sakai et al.			
	4,294,650	10/13/1981	Werthmann			
	3,923,566	12/02/1975	Law			
	5,259,926	11/09/1993	Kuwabara et al.			
	5,425,848	06/20/1995	Haisma et al.			
	5,503,963	04/02/1996	Bifano			
	4,543,225	09/24/1985	Beaujean			
↓	5,434,107	07/18/1995	Paranjpe			
BT	5,338,396	08/16/1994	Abdala et al.			

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EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

BT			Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> 145-149, (1992)
BT			Nomura, et al., "Moire Alignment Technique for the Mix and Match Lithographic System: <u>J. Vacuum Society Technol. B6</u> (1), American Vacuum Society, 394-398, (Jan/Feb 1988)

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ATTY DOCKET NO.
14002-7

SERIAL NO.
TBD

Chou et al.

FILING
November 12, 2003

GROUP
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U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

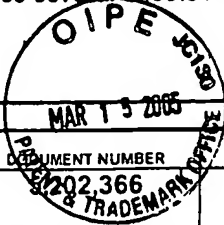
3A	Healey et al., "Photodeposition of Micrometer-scale polymer patterns on optical imaging Fibers" Science Vol. 269, No. 25, August 1995, pp. 1078-1080.

EXAMINER *Minh Tran*

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INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)



Docket Number (Optional)

14002-7

Application Number

10/706,757

Applicant(s)

Stephen Y. Chou, et al.

Filing Date

November 12, 2003

Group Art Unit

1765

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EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BT		202,366	04/13/93	Reid et al.	523	516	
BT		2001/0040145	11/15/01	Willson et al.	216	52	

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	REF	DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							Yes	No
BT		WO 02/03142	10-01-02		G03F	7/00		
BT		62214531	21-09-87		G11B	7/24		

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BT		Schulz, et al., "Low-Temperature Wafer-Scale 'WARM' Embossing for Mix & Match with UV-Lithography", 2002, Proceedings of SPIE, Vol. 4688, pgs. 223-231	
BT		Khang, et al., "Room-temperature imprint lithography by solvent vapor treatment", February 14, 2000, Applied Physics Letters, Vol. 76, No. 7, pgs. 870-872	
		Lebib, A., et al., "Room-temperature and low-pressure nanoimprint lithography", 2002, Microelectronic Engineering, 61-62, pgs. 371-377	
		Pfeiffer, K., et al., "Suitability of new polymer materials with adjustable glass temperature for nano-imprinting", 1999, Microelectronic Engineering, 49, pgs. 431-434	
		Haisma, et al., "Mold-assisted nanolithography: A process for reliable pattern replication", Nov/Dec 1996, J. VA. Sci. Technol. B 14(6), pgs. 4124-4128	
BT		Zwiers, et al., "Aspherical lenses produced by a fast high-precision replication process using UV-curable coatings", December 15, 1985, Applied Optics, Vol. 24, No. 24, pgs. 4483-4488	

Examiner

Bink Trun

Date Considered

3/3/06

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Form PTO-A820 (also form PTO-1449)